THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of

Shunpei YAMAZAKI et al.

Serial No. 09/535,015

Filed: March 24, 2000

For: METHOD OF MANUFACTURING

A SEMICONDUCTOR DEVICE

) Group Art Unit: 2811

) Examiner: S. Crane

## **CERTIFICATE OF MAILING**

I hereby certify that this correspondence is being deposited with The United States Postal Service with sufficient postage as First Class Mail in an envelope addressed to: Commissioner for Patents, Washington, D.C. 2023 1, on 4-11-2008.

Udile M Stamper Adele M. Stamper

Honorable Commissioner for Patents

Washington, D.C. 20231

Sir:

SUPPLEMENTAL AMENDMENT

TECHNOLOGY CENTER 2003

TECHNO Amendment filed February 24, 2003, please amend the above-identified application as follows:

## IN THE SPECIFICATION:

Please amend the specification as follows:

Please replace the paragraph bridging page 4 and 5 with the following:

According to the present invention disclosed in the present specification, chlorine is also contained in the atmosphere in order to promote the effect of gettering the metal. The effect of eliminating the metal element from the silicon film may be enhanced by forming a compound of the metal element, fluorine and chlorine at the time of gettering by introducing chlorine.